

Supporting Information

Selective Enriching of Trionic Emission in a WS₂-ZnO Hybrid through Type-II Band Alignment

Jin Feng LEONG¹, Kim Yong LIM¹, Xiao WU², Qing Hua XU², Chornng Haur SOW¹, Eng Tuan POH^{1*}

¹Department of Physics, National University of Singapore, 2 Science Drive 3, Singapore 117551

²Department of Chemistry, National University of Singapore, 3 Science Drive 3, Singapore 117543

*E-mail: phyetp@nus.edu.sg

Table S1: Benchmark table across multiple substrates for trion enhancement in monolayer WS₂

	Laser power density (MW/cm ²)	I _{exciton} /I _{trion}
Suspended/Free-standing ^[1]	0.01	1:0.25
Al ₂ O ₃ ^[2]	0.3	1:0.62
Au ^[2]	0.3	1:0.42
hBN ^[3]	0.24	1:0.0375
Graphene ^[4]	- [*]	1:0
SiO ₂ (Our work)	0.01	1:0.44
ZnO (Our work)	0.01	1:0.54
ZnO (Our work)	0.1	1:1.09

^{*}While this work did not indicate the laser power used, they did present a reference WS₂ sample on SiO₂/Si, which shows trion to exciton ratio of ~1:0.25. Assuming that the laser power used to measure both samples are the same, we can deduce that the trion emission should be quenched by graphene.

Reference

[1] Harats M G et al., Kirchof J N et al., Qiao M et al. Dynamics and efficient conversion of excitons to trions in non-uniformly strained monolayer WS₂, Nat. Pho., 2020, 14, 324–329.

[2] Das S et al., Chowdhury R K et al., Karmakar D et al. Substrate-dependent synergistic many-body effect in atomically thin two-dimensional WS₂, Phys. Rev. Materials, 2021, 5, 124001.

[3] Yusuke H et al., Kuroda T et al., Okada M et al. Suppression of exciton-exciton annihilation in tungsten disulfide monolayers encapsulated by hexagonal boron nitride, Phys. Rev. B, 2017, 95, 241403.

[4] Kobayashi Y et al., Sasaki S et al., Mori S et al. Growth and Optical Properties of High-Quality Monolayer WS₂ on Graphite, ACS Nano., 2015, 9(4), 4056–4063.

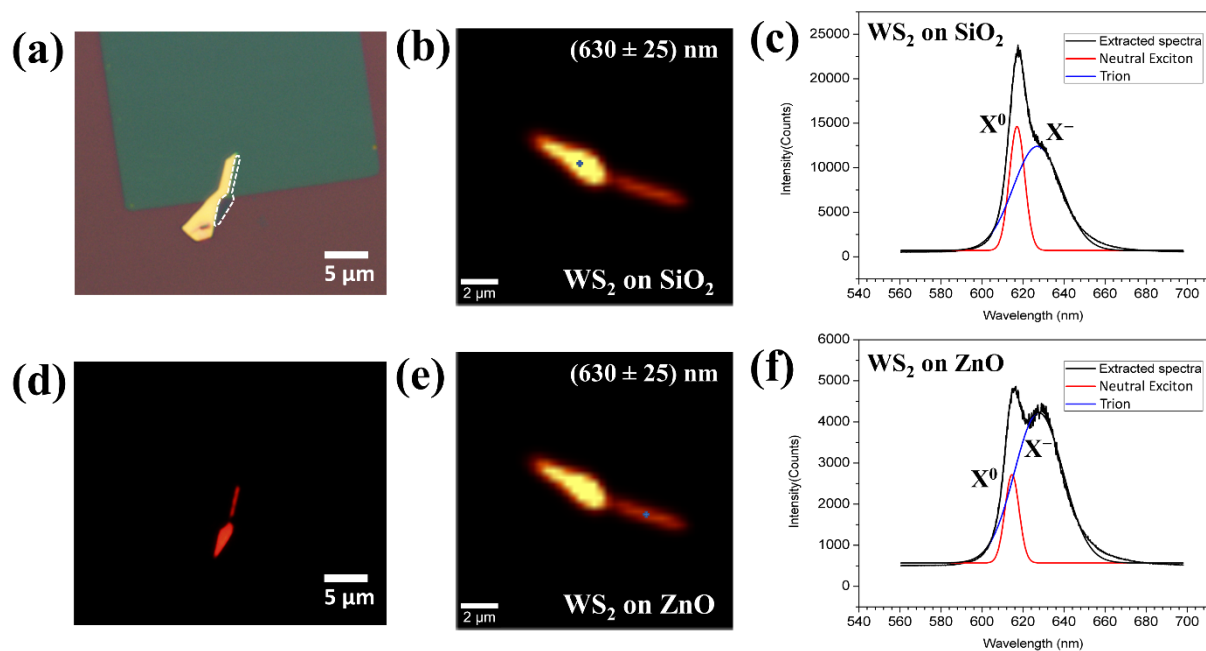


Figure S1. Reproducibility Test and Characterization Upon A Second WS₂-ZnO Heterostructure. (a) Optical microscopy image of the WS₂-ZnO heterostructure formed from exfoliated WS₂ placed onto a ZnO square film. (b) PL map of the fluorescence distribution for the monolayer region over (630 ± 25) nm, with the marked-out spot location corresponding to the spectrum acquired in (c). (c) PL spectrum for the WS₂ on SiO₂ spot marked in (b), deconvoluted of the exciton trion components. (d) Fluorescence micrograph demonstrating the uniform emission distribution over the monolayer region of the sample. (e) PL map of the fluorescence distribution for the monolayer region over (630 ± 25) nm, with the marked-out spot location corresponding to the spectrum acquired in (f). (f) PL spectrum for the WS₂ on ZnO spot marked in (e), demonstrating the increased trion contribution.

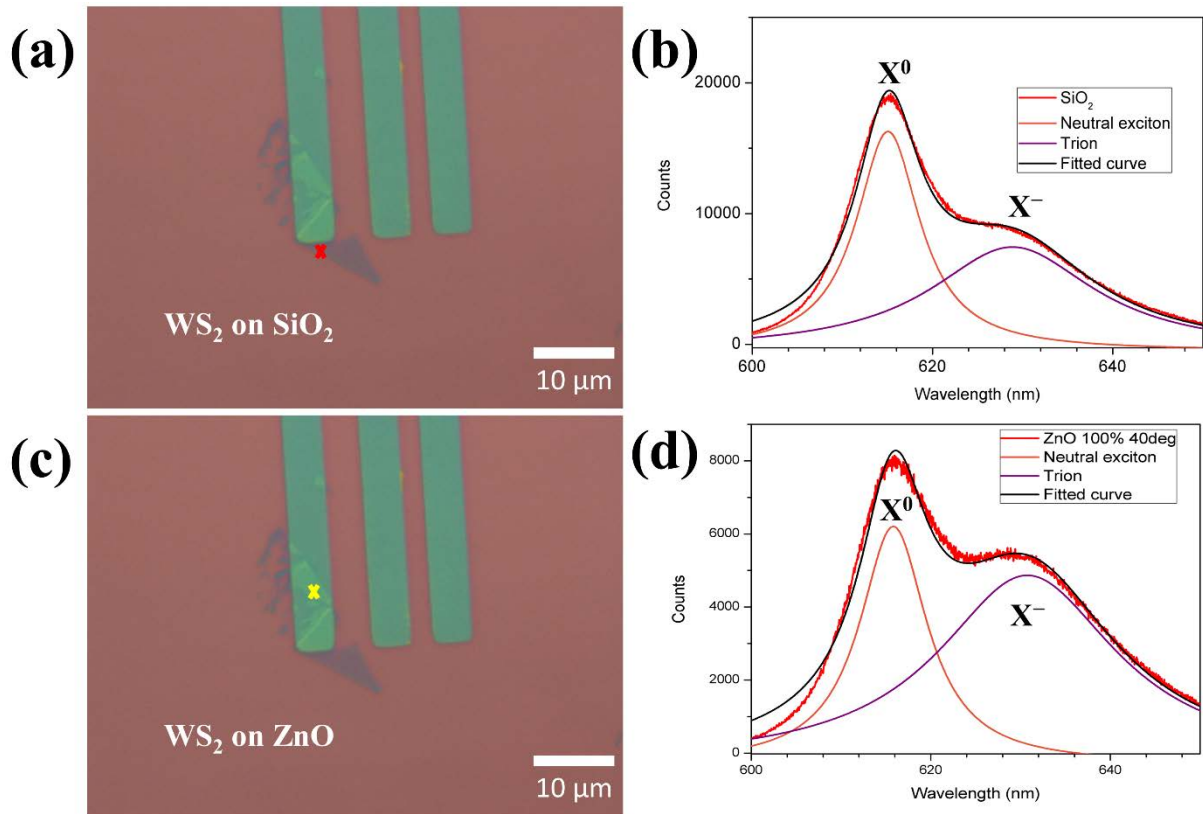


Figure S2. Reproducibility Test and Characterization Upon A Third WS₂-ZnO Heterostructure. (a) Optical microscopy image of the WS₂-ZnO heterostructure constructed upon emplacement of the exfoliated WS₂ atop the ZnO finger array. Spot marked with red “x” corresponds to where the PL spectrum in (b) was acquired from. (b) PL spectrum for the WS₂ on SiO₂ spot marked in (a), deconvoluted of the exciton trion components. (c) Optical microscopy image of the WS₂-ZnO heterostructure constructed upon emplacement of the exfoliated WS₂ atop the ZnO finger array. Spot marked with yellow “x” corresponds to where the PL spectrum in (d) was acquired from. (d) PL spectrum for the WS₂ on ZnO spot marked in (c), demonstrating the increased trion contribution.

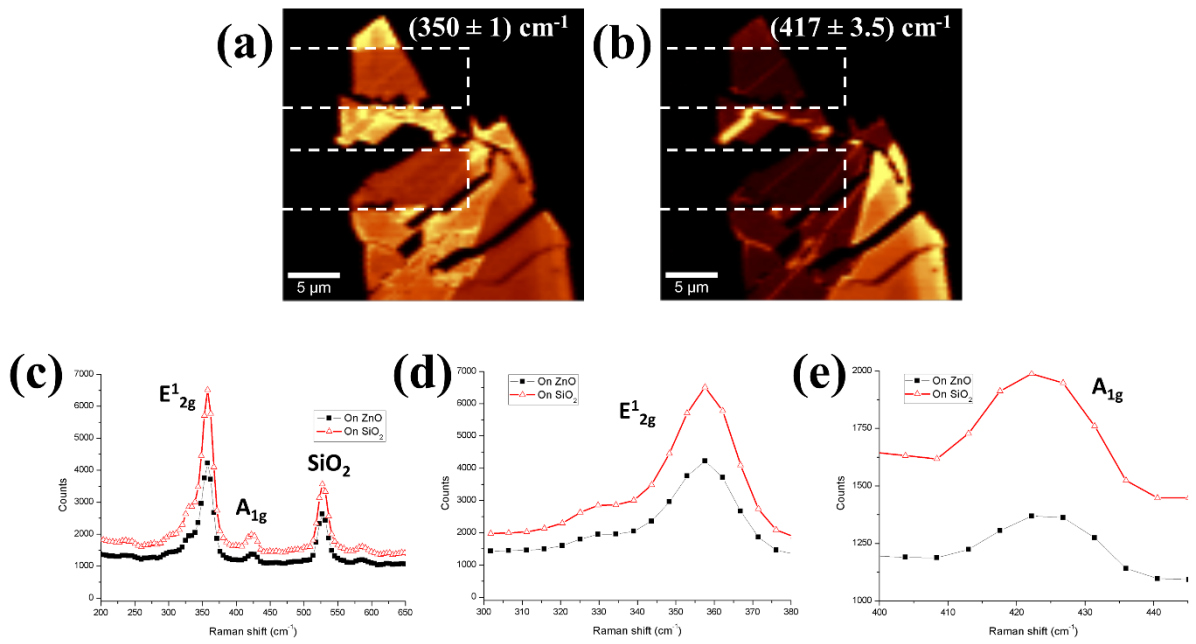


Figure S3. Raman Characteristics of the WS₂-ZnO Heterostructure. (a) Raman mapping across the heterostructure domain spanning the wavenumber range of $(350 \pm 1) \text{ cm}^{-1}$, corresponding to the E_{12g} phonon active mode of WS₂ in-plane vibration. (b) Raman mapping across the heterostructure domain spanning the wavenumber range of $(417 \pm 3.5) \text{ cm}^{-1}$, corresponding to the A_{1g} phonon active mode of WS₂ out-of-plane vibration. (c) Overall Raman spectra comparison for WS₂ on SiO₂ and WS₂ on ZnO, detailing the E_{12g}, A_{1g} and SiO₂ peaks. (d) Magnified Raman spectra feature around E_{12g} signal, detailing the difference in peak intensity for the WS₂ samples on the different substrates. (e) Magnified Raman spectra feature around A_{1g} signal, detailing the difference in peak intensity for the WS₂ samples on the different substrates.

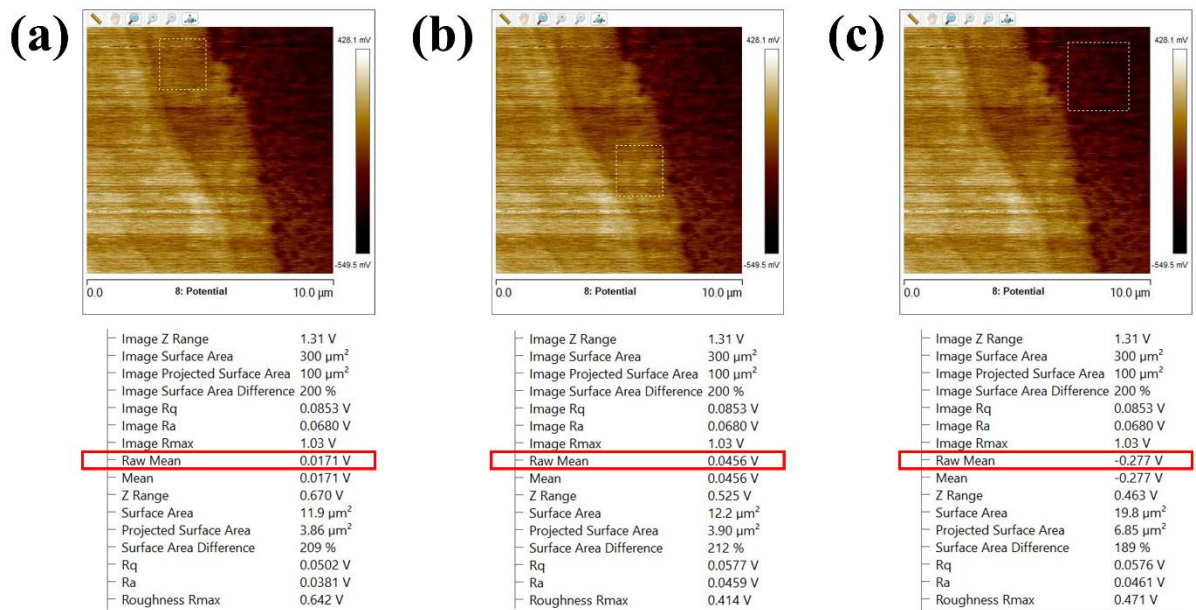


Figure S4. KPFM Statistics for the WS₂-ZnO Heterostructure at Different Sample Domains. (a) Averaged measurement details for WS₂ on Si sample region marked by dashed white square in the KPFM scan map. (b) Averaged measurement details for WS₂ on ZnO overlay heterostructure region marked by dashed white square in the KPFM scan map. (c) Averaged measurement details for ZnO on Si sample region marked by dashed white square in the KPFM scan map. Red rectangular outlines in the measurement statistics highlight the contact potential difference (CPD) acquired for each sample zone with respect to the applied tip potential. The relative sample work function can be acquired from the difference in CPD between WS₂ on Si and ZnO on Si.

(a)

SiO ₂ Exciton	Value	Standard Error
$E_g(0)$	2.08	2.86E-03
α	3.78E-04	5.38E-05
β	166.86	81.48
No. of Points	7	
Degrees of Freedom	4	
Reduced Chi-Sqr	2.00E-06	
Residual Sum of Squares	8.00E-06	
Adj. R-Square	0.997	

(b)

SiO ₂ Trion	Value	Standard Error
$E_g(0)$	2.04	3.60E-03
α	6.21E-4	4.32E-05
β	472.66	0
No. of Points	7	
Degrees of Freedom	5	
Reduced Chi-Sqr	2.38E-05	
Residual Sum of Squares	1.19E-04	
Adj. R-Square	0.971	

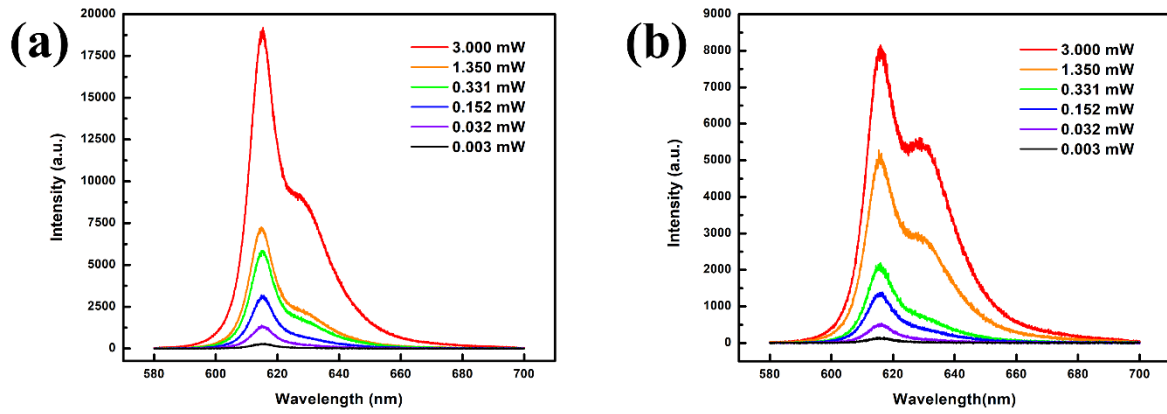
(c)

ZnO Exciton	Value	Standard Error
$E_g(0)$	2.08	2.53E-03
α	6.80E-04	3.04E-04
β	588.98	423.32
No. of Points	7	
Degrees of Freedom	4	
Reduced Chi-Sqr	3.29E-06	
Residual Sum of Squares	1.32E-05	
Adj. R-Square	0.996	

(d)

ZnO Trion	Value	Standard Error
$E_g(0)$	2.02	2.51E-03
α	4.84E-4	3.20E-05
β	520.66	0
No. of Points	7	
Degrees of Freedom	5	
Reduced Chi-Sqr	1.17E-05	
Residual Sum of Squares	5.84E-05	
Adj. R-Square	0.974	

Figure S5. Data Modelling Statistics for Exciton and Trion Energies of WS₂ on SiO₂ and WS₂ on ZnO Samples under the Varshni Relation. (a) Fitting statistics for excitons in the WS₂ on SiO₂ sample under Varshni modelling. (b) Fitting statistics for trions in the WS₂ on SiO₂ sample under Varshni modelling. (c) Fitting statistics for excitons in the WS₂ on ZnO sample under Varshni modelling. (d) Fitting statistics for trions in the WS₂ on ZnO sample under Varshni modelling.



Excitation Power (mW)	WS ₂ on SiO ₂				WS ₂ on ZnO			
	I _{Exciton}	I _{Trion}	I _{Trion} /I _{Exciton}	Ratio	I _{Exciton}	I _{Trion}	I _{Trion} /I _{Exciton}	Ratio
3.000	11851	8777	0.7406	2.506	4538	4976	1.0965	4.615
1.350	4981	2300	0.4618	1.562	2987	2743	0.9183	3.865
0.331	3949	1752	0.4437	1.501	1362	745	0.5470	2.302
0.152	2306	803	0.3482	1.178	967	417	0.4312	1.815
0.032	1001	295	0.2947	0.997	379	118	0.3113	1.310
0.003	203	60	0.2955	1.000	101	24	0.2376	1.000

Figure S6. PL Spectra Evolution for the WS₂ on SiO₂ and WS₂ on ZnO Samples under Variable Excitation Powers. (a) Spectra evolution for WS₂ on SiO₂ sample under 532 nm excitation power variation ranging from 0.003 mW to 3.000 mW. (b) Spectra evolution for WS₂ on ZnO sample under 532 nm excitation power variation ranging from 0.003 mW to 3.000 mW. Table below tallies the peak intensities for excitons, trions, trion-to-exciton metric ratio and ratio normalized against the lowest baseline excitation power (0.003 mW), for WS₂ on SiO₂ and WS₂ on ZnO samples respectively.